EAST - [Default EAST Workspace (Flat Panel LANDSCAPE).wsp:1]

File View Edit Tools Window Help

- Drafts
- Pending
- Active
  - L1: (2) (("6596655") or ("6348725")).PN.
  - L2: (24140) low near (dielectric or constant
  - L3: (189) 2 and organosiloxane$1
  - L4: (118) 3 and cyclic
  - L5: (83) 4 and dielectric.clm.
  - L6: (55) 5 and (RF near power)
  - L7: (15) 6 and ((ring or cyclic) near organo
  - L8: (2) (("5976979") or ("6124641")).PN.
  - L9: (19) (("6,642,157") or ("6,596,655") or
  - L10: (0) 9 and precusor$1
  - L11: (14) 9 and precursor$1
  - L12: (5) 11 and organosi$5
  - L13: (13) (("6,331,494") or ("6,312,793") or
  - L14: (5) 13 and organosi$6
  - L15: (3) 14 and (low near dielectric)
- Failed
- Saved
  - (8) (("6475874") or ("6372561") or ("6365445
  - (5) (("6524954") or ("6475874") or ("6316362

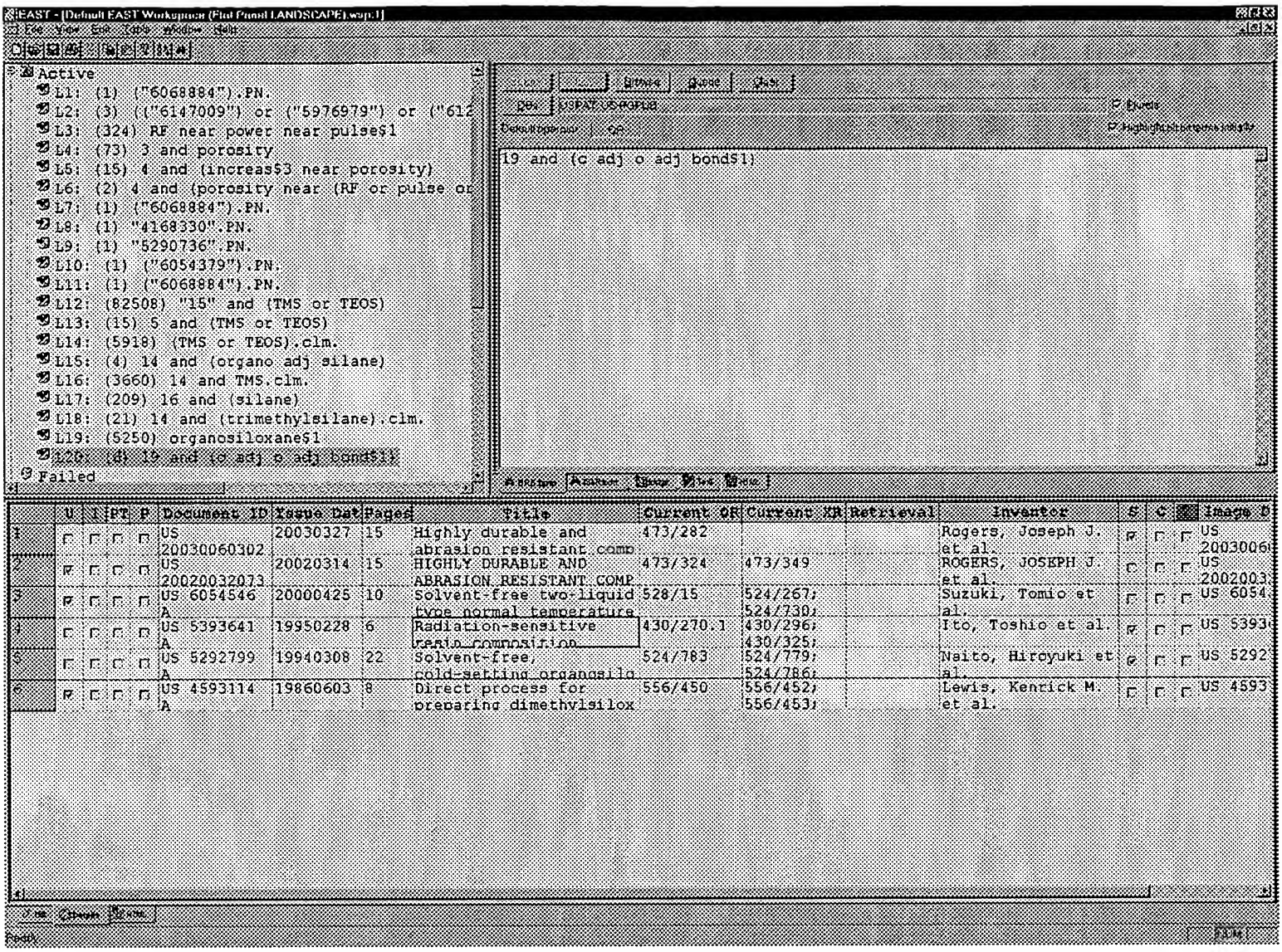
DBs: USPAT; US-PGPUB

Default operator: OR

14 and (low near dielectric)

	U	I	PT	P	Document ID	Issue Date	Pages	Title	Current OR	Current XR	Retrieval	Inventor	S	C		Image D
1	☐	☑	☐	☐	US 6147009 A	20001114	11	Hydrogenated oxidized silicon carbon material	438/780	257/E23.11 9;		Grill, Alfred et al.	☑	☐	☐	US 6147
2	☐	☐	☐	☐	US 6068884 A	20000530	14	Method of making low .kappa. dielectric inor	427/255.6	257/E21.26 ;		Rose, Peter et al.	☑	☐	☐	US 6068
3	☐	☐	☐	☐	US 5989998 A	19991123	21	Method of forming interlayer insulating f	438/623	257/E21.26 1;		Sugahara, Gaku et al.	☑	☐	☐	US 5989

Ready


EAST - [Default EAST Workspace (Flat Panel LANDSCAPE).wsp:1]
File View Set Tools Window Help
Active
L1: (1) ("6068884").PN.
L2: (3) (("6147009") or ("5976979") or ("612
L3: (324) RF near power near pulse$1
L4: (73) 3 and porosity
L5: (15) 4 and (increas$3 near porosity)
L6: (2) 4 and (porosity near (RF or pulse or
L7: (1) ("6068884").PN.
L8: (1) "4168330".PN.
L9: (1) "5290736".PN.
L10: (1) ("6054379").PN.
L11: (1) ("6068884").PN.
L12: (82508) "15" and (TMS or TEOS)
L13: (15) 5 and (TMS or TEOS)
L14: (5918) (TMS or TEOS).clm.
L15: (4) 14 and (organo adj silane)
L16: (3660) 14 and TMS.clm.
L17: (209) 16 and (silane)
L18: (21) 14 and (trimethylsilane).clm.
L19: (5250) organosiloxane$1
L20: (4) 19 and (c adj o adj bond$1)
Failed
19 and (c adj o adj bond$1)
U I PT P Document ID Issue Dat Pages Title Current OR Current XR Retrieval Inventor S C Image
1 US 20030060302 20030327 15 Highly durable and abrasion resistant comp 473/282 Rogers, Joseph J. et al. US 2003006
2 US 20020032073 20020314 15 HIGHLY DURABLE AND ABRASION RESISTANT COMP 473/324 473/349 ROGERS, JOSEPH J. et al. US 2002003
3 US 6054546 A 20000425 10 Solvent-free two-liquid type normal temperature 528/15 524/267; 524/730; Suzuki, Tomio et al. US 6054
4 US 5393641 A 19950228 6 Radiation-sensitive resin composition 430/270.1 430/296; 430/325; Ito, Toshio et al. US 5393
5 US 5292799 A 19940308 22 Solvent-free, cold-setting organosilo 524/783 524/779; 524/786; Naito, Hiroyuki et al. US 5292
6 US 4593114 A 19860603 8 Direct process for preparing dimethylsilox 556/450 556/452; 556/453; Lewis, Kenrick M. et al. US 4593